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	Applicat	ion No.	Applicant(s)	
	10/720,8	51	UESAWA, FUMIKAT	su
Notice of Allowability	Examine	r	Art Unit	
	Stephen	W. Smoot	2813	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REM/ 5) or other a <b>RIGHTS</b> . Th	AINS) CLOSED in the ppropriate communion ppropriate communion is subj	is application. If not include cation will be mailed in due o	d course. <b>THIS</b>
1. $igotimes$ This communication is responsive to <u>applicant's amendm</u>	ent filed on	01 June 2005.		
2. X The allowed claim(s), is/are 1-4,8,10-15 and 17-27.				
3. $igotimes$ The drawings filed on <u>24 November 2003</u> are accepted by	y the Exami	ner.		
4. Acknowledgment is made of a claim for foreign priority of a) All b) Some* c) None of the:  1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 1. International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDONI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be submined in the submined part of the priority of the Notice of Draftsper (a) including changes required by the Notice of Draftsper (b) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examined Paper No./Mail Date (b) Including changes required by the attached Examined Paper No./Mail Date (b) Deposit Of and/or INFORMATION about the deposit of the priority of the deposit of the priority of the deposit of the priority of the deposit of	ve been receive been receive been receive ocuments here.  " of this comment of this mitted. Note wes reason with the submirson's Pater of the comment of the header of the	eived. Eived in Application Nave been received in Application Nave been received in Application to file as application.  The attached EXAM s) why the oath or defitted.  Int Drawing Review ( Interpretation on the eaccording to 37 CFR	No. 10/154,237 In this national stage applicate reply complying with the required stage applicate reply complying ap	puirements OTICE OF
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT</li> </ol>	osit of BIO T FOR THE	LOGICAL MATER DEPOSIT OF BIOLO	IAL must be submitted. N DGICAL MATERIAL.	Note the
Attachment(s)  1. ☐ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB. Paper No./Mail Date  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	3/08),	6. Interview Sum Paper No./Ma 7. Examiner's Ar	mal Patent Application (PTC mary (PTO-413), ail Date nendment/Comment atement of Reasons for Allo	·
Stephen	nW,	Smoot	Stephen W. Smoot Patent Examiner Art Unit 2813	

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## **DETAILED ACTION**

This Office action is in response to applicant's amendment filed on 01 June 2005.

## Allowable Subject Matter

- 1. Claims 1-4, 8, 10-15, 17-27 are allowed.
- 2. The following is an examiner's statement of reasons for allowance:
  - Claims 1-4, 8, 10-15 are allowed because the prior art of record does not teach
    or suggest, in combination with the other claim limitations, a method of
    manufacturing a semiconductor apparatus that includes forming a tapered
    aperture pattern in a first mask material and using the first mask material to
    vertically etch an aperture into a film with a dimension that exceeds the
    capabilities of lithography techniques, wherein the tapered aperture is formed at
    a temperature between minus 50 and zero degrees Centigrade;
  - Claims 17-26 are allowed because the prior art of record does not teach or suggest, in combination with the other claim limitations, a method of manufacturing a semiconductor apparatus that includes forming a tapered aperture pattern in a first mask material and using the first mask material to

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vertically etch an aperture into a film with a dimension that exceeds the capabilities of lithography techniques, wherein the first mask material is made of an organic insulation film and has a heatproof temperature of about 350 degrees Centigrade; and

• Claim 27 is allowed because the prior art of record does not teach or suggest, in combination with the other claim limitations, a method of manufacturing a semiconductor apparatus that includes forming a tapered aperture pattern in a first mask material and using the first mask material to vertically etch an aperture into a film with a dimension that exceeds the capabilities of lithography techniques, wherein the film has portions with different thicknesses that define a step and wherein the first mask material planarizes an unevenness created by the step.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stephen W. Smoot whose telephone number is 571-272-1698. The examiner can normally be reached on M-F (8:00 am to 4:30 pm).

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system; contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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